Advancing Industry Productivity

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Joint Productivity Working Group Session

Austin, Texas Thursday, October 12, 2006



think it. apply it.

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• Why are we here?

What have we done?

Is there a basis for moving forward?

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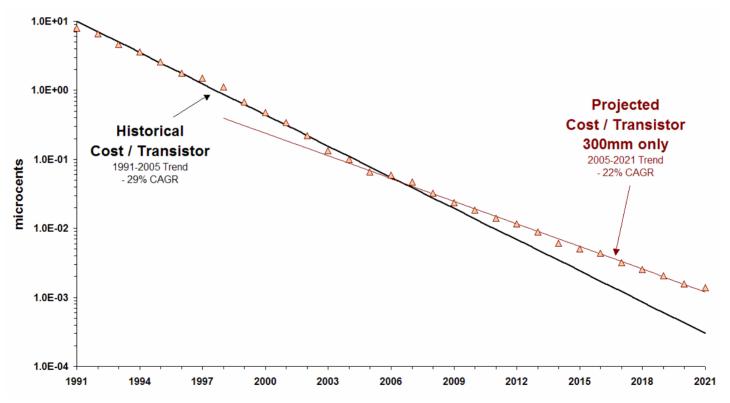
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The "Productivity" Challenge

Average Fab Costs per Transistor



Source: ISMI

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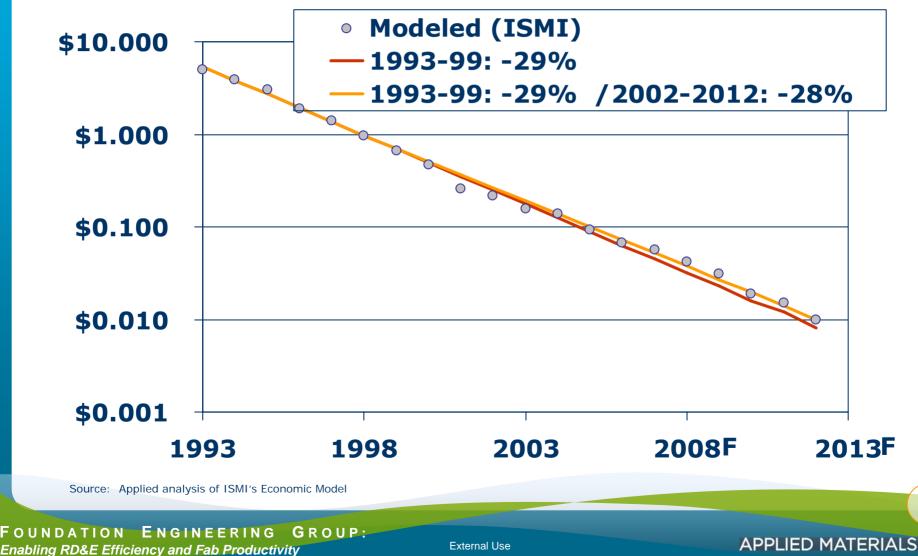
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The Challenge... Revisited

Average Fab Costs (µ-¢/transistor)



Oh, By the Way



- The standard deviation of the annual transistor cost trend is 12%
- A 1%-2% difference in slopes is statistically insignificant
- A 1%-2% difference in slopes is also minuscule compared to the level of uncertainly in the thousands of assumptions built into the ISMI Economic Model

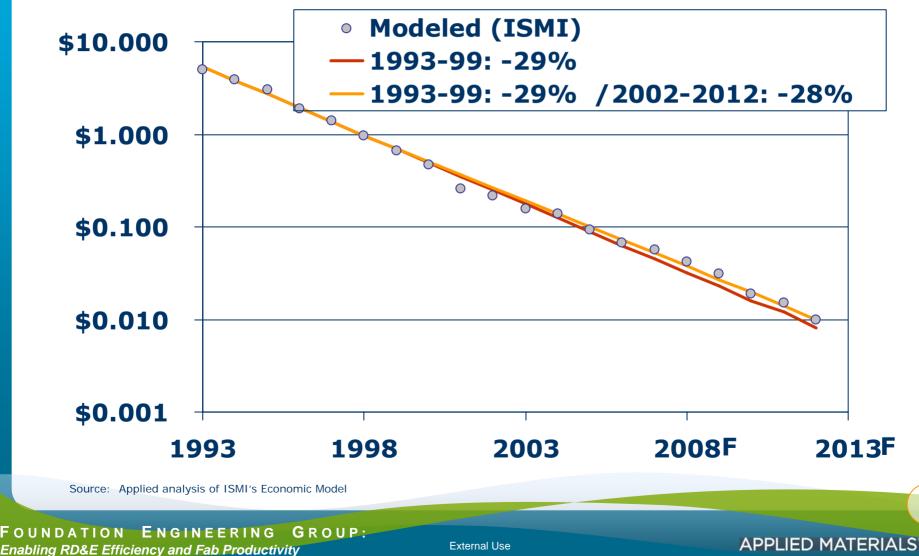




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The Challenge... Revisited

Average Fab Costs (µ-¢/transistor)

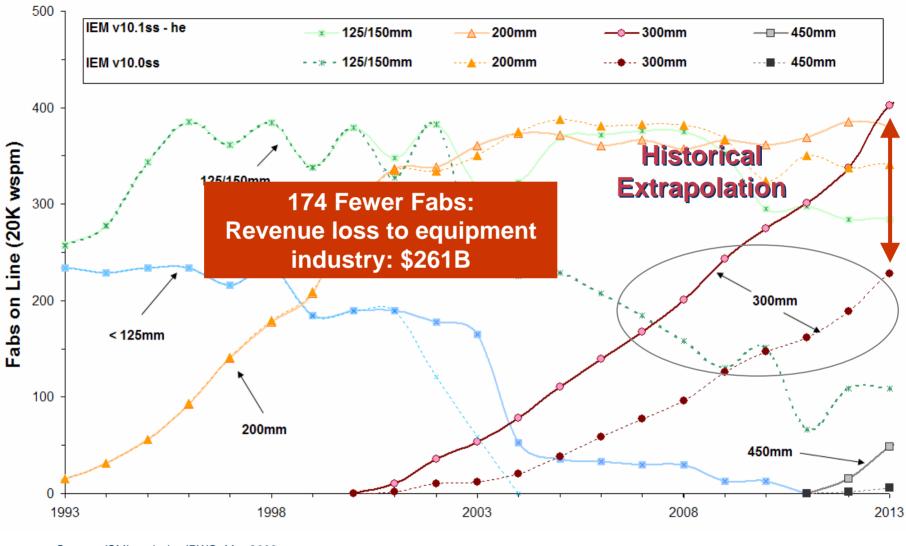




The Challenge... Interpreted

- We have "discovered"—and confirmed via sensitivity analysis—the root cause of the (minor) shift of the 2000's
- In order to extend the extraordinarily rapid rate of reduction in cost/ transistor during the late 1990's...
- ... we need to extend the extraordinary market/economic conditions of the late 1990's
 - Rapid demand growth
 - ... funding accelerated technology progress
- We can't extrapolate the effect without extrapolating the cause!

Economic Implications



Source: ISMI analysis, JPWG, May 2006

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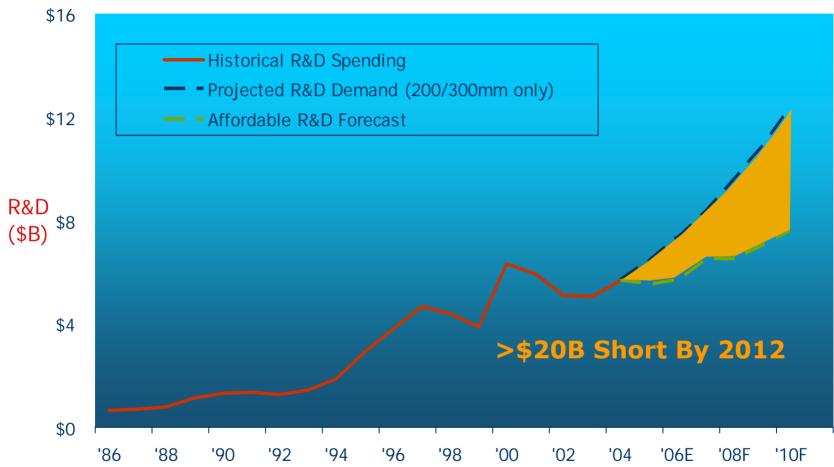
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Equipment R&D Gap



Note: Affordable R/D forecast assumes 14% of equipment industry revenues Sources: S&P, SIA, SEMI, Infrastructure Advisors

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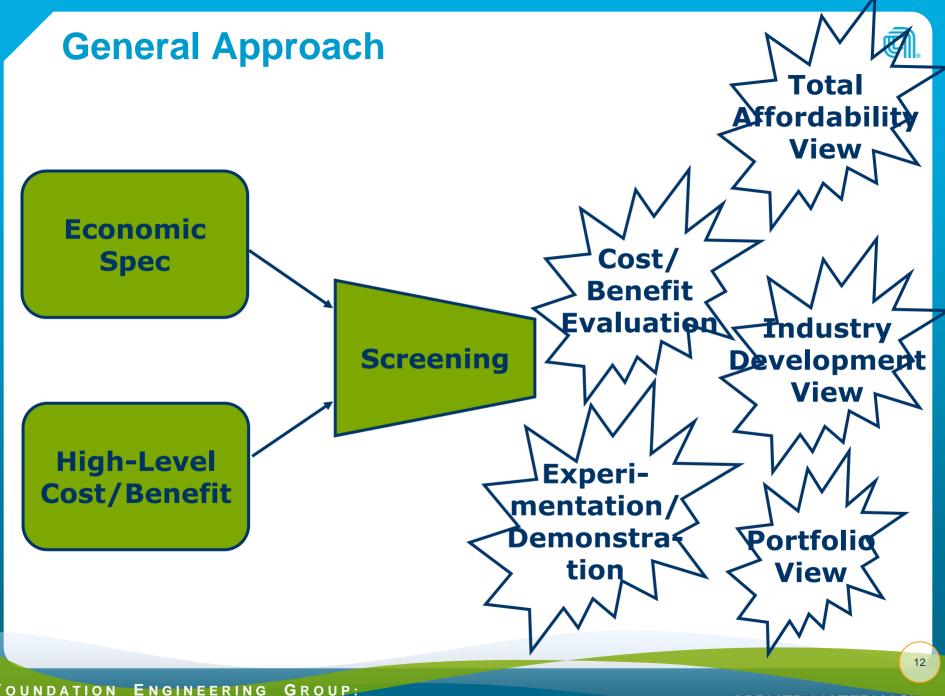
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Spec for the Analytical Tool



- Simple, transparent models
 - few variables
 - less "precise" but more accurate... and correct
 - easy/quick to calculate and adjust
- Single vertically-integrated company
- Affordable investment based on cost/benefits and expected risks and return





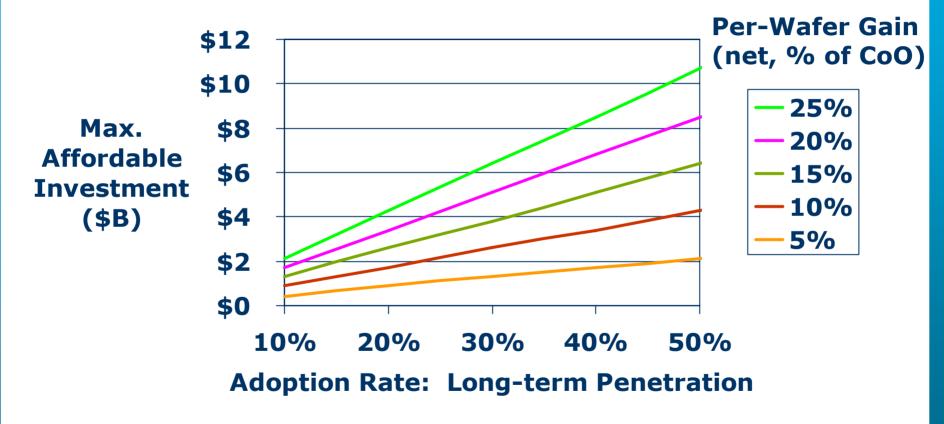
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Economic Context for Fab Initiatives



Note: 20% required rate of return; 7-year development time

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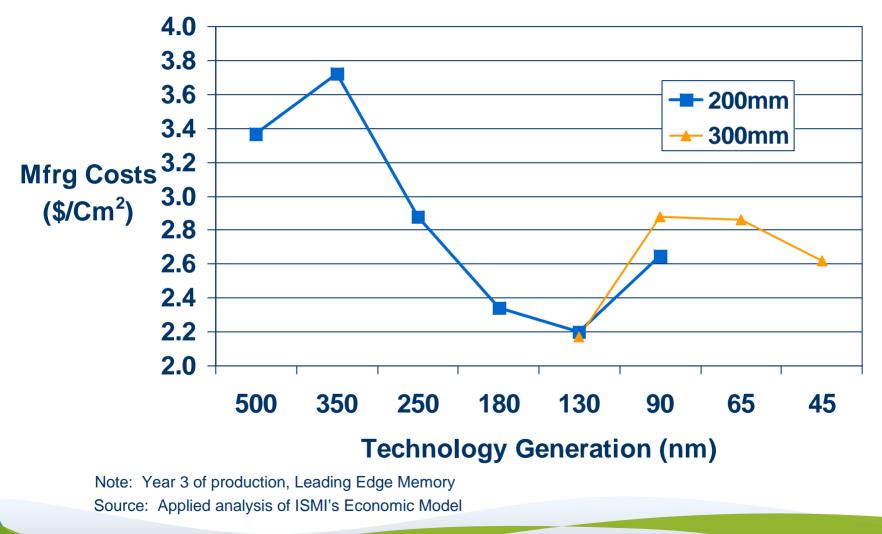
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Economic Impact of Wafer Size Transition



Manufacturing Cost Trend



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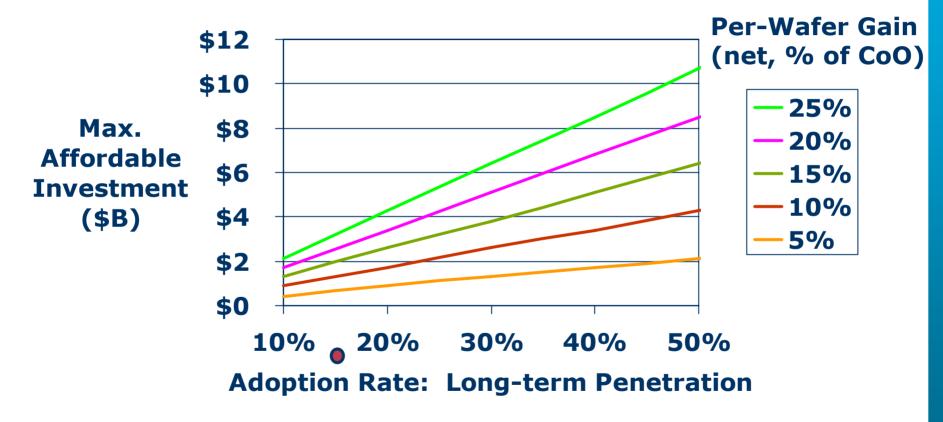
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Case 1: Implications: 450mm



Economic Context for Fab Initiatives



Note: 20% required rate of return; 7-year development time

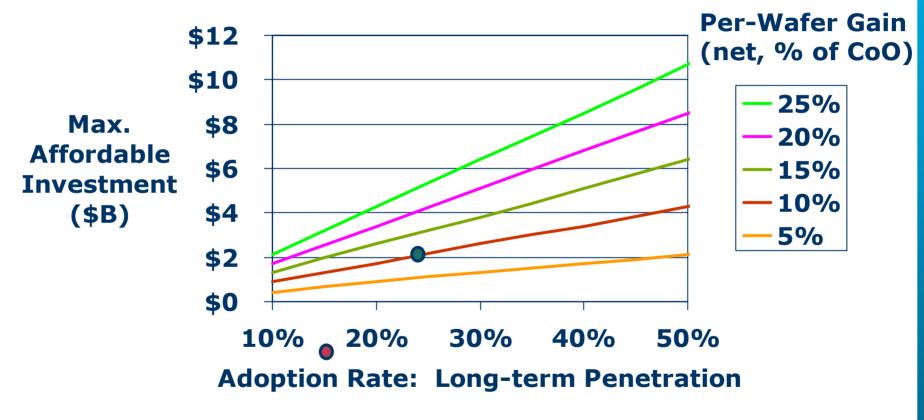
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Economic Context for Fab Initiatives



Note: Illustration of small-lot impact

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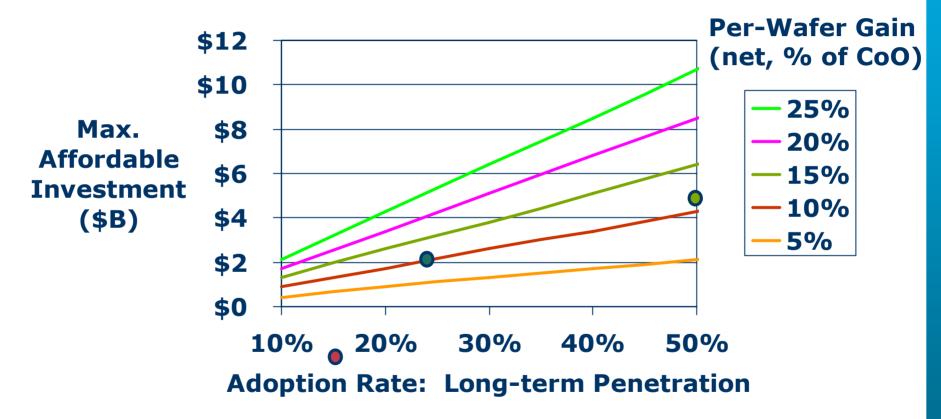
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Case 3: Technology Cost/Benefit



Economic Context for Fab Initiatives



Note: Illustration of one-time, 1-year acceleration in pace of technology

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Summary of JPWG Status (1/2)



Торіс	Agreement	Disagreement
Slope of cost per xtor vs. time trend	Not changing from -29% to -22%	Changing to -26% or -28%
Root cause for slow down in decline of cost per transistor vs. time	Pace of technology advance (as funded by demand growth)	
R&D Funding Gap	R&D gap is increasing, requiring us to set priorities	What is key concern: Only IC maker R&D, or IC maker & equipment supplier
300 mm Prime	This should be the focus of the industry	300mm Prime is a 300mm productivity program, or a 450mm transition plan
New initiative proposals	Screen with simple, transparent model – intrinsic cost /benefit, rate of penetration and investment	Benefits: industry-wide or sector silo/parochial view IEM as golden standard, or as a tool to be tested/challenged

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Summary of JPWG Status (2/2)



Topic	Agreement	Disagreement
Industry Productivity	Continuous improvement is critical to the industry	Definition of "productivity" •Cost per unit area •Cost per transistor •Cost per function • Entitlement: technology advancement, or other sources Productivity goals: edict or analysis

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ISMI Economic Model



- Demand level & mix (from Semico)
 - + assumed technology & productivity trends
 - \rightarrow capacity allocation to installed base of fabs
 - \rightarrow invest to bridge gap
 - \rightarrow overlay business cycle
- Very large # of assumptions, some of which are not verifiable
- Fab owner perspective
- Static fab model
- Top-down, centrally planned, no competition
- Limited data for most advanced processes



